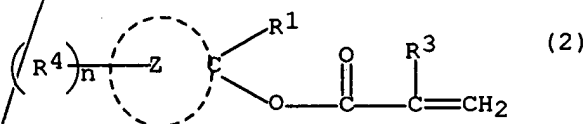


wherein R^1 represents a hydrogen atom, an alkyl group or a cycloalkyl group; R^2 represents an alkyl group or a cycloalkyl group; R^3 represents a hydrogen atom or a methyl group; R^4 represents a hydrogen atom, a halogen atom, an alkyl group, an oxygen-containing group, an amino group or an N-substituted amino group; n represents an integer of not less than 1; with proviso that all R^4 s are not concurrently hydrogen atoms, and R^4 may be varied according to n ; the Z ring represents an adamantane ring; R^1 and R^2 may, jointly and together with adjacent carbon atom, form an alicyclic hydrocarbon ring,

or by the following formula (2)



wherein R^1 represents an alkyl group or a cycloalkyl group; R^3 represents a hydrogen atom or a methyl group; R^4 represents a hydrogen atom, a halogen atom, an alkyl group, an oxygen-containing group, an amino group or an N-substituted amino group; n represents an integer of not less than 1; with proviso that R^4 may be varied according to n ; and Z represents an adamantane ring,

wherein at least one of the R^4 s in formula (1) and at least one of R^4 s in formula (2) is an oxygen-containing group selected from the group consisting of oxo groups, hydroxyl groups, alkoxy groups, carboxyl groups, alkoxycarbonyl groups, cycloalkyloxycarbonyl groups, aryloxycarbonyl groups, aralkyloxycarbonyl

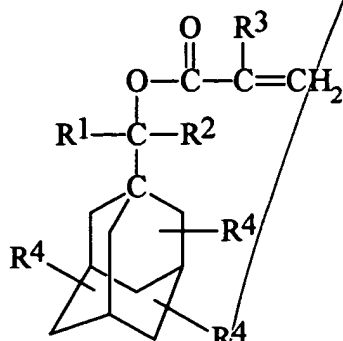
D1
E1
groups, hydroxymethyl groups, carbamoyl groups, N-substituted carbamoyl groups, and nitro groups.

D2
Sub
E2
2. (amended) The acid-responsive compound according to Claim 1 having the formula (1), wherein R¹ is a hydrogen atom and R² is a straight-chain or branched-chain C₁₋₄alkyl group.

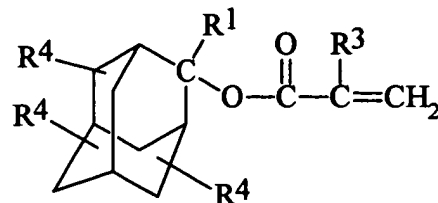
5. The acid-responsive compound according to Claim 1 wherein R⁴ is a hydroxyl group, an alkoxy group, a carboxyl group, an alkoxycarbonyl group or a hydroxymethyl group.

6. The acid-responsive compound according to Claim 1 wherein R⁴ is a hydroxyl group or a carboxyl group and n is an integer of 2 to 4.

D3
E3
7. (amended) The acid-responsive compound according to Claim 1, which is represented by the following formula (1a) or (2a):



(1a)

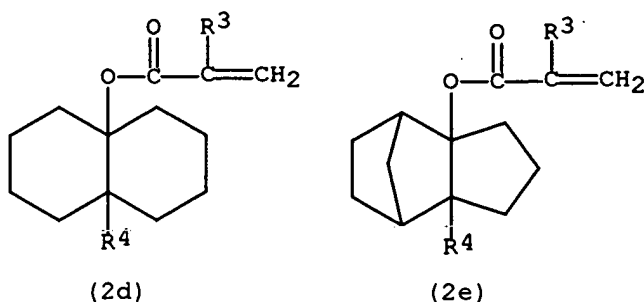


(2a)

wherein R¹, R² and R³ are as defined above; and the R⁴s may be the same or different from each other and each represents a hydrogen atom, a halogen atom, an alkyl group, an oxygen-containing group, an amino group or an N-substituted amino group.

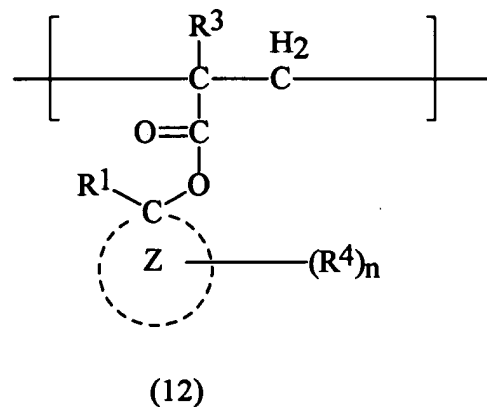
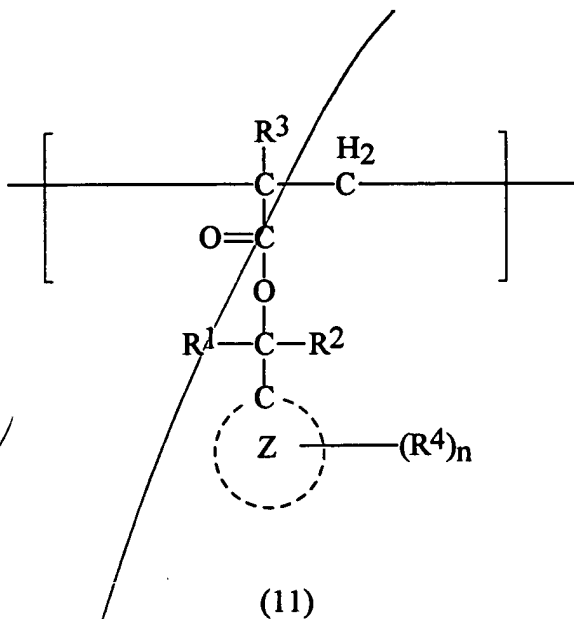
8. (amended) The acid-responsive compound according to Claim 7, wherein R¹ in formula (1a) is a hydrogen atom or a straight-chain or branched-chain C₁₋₄ alkyl group, and R¹ in formula (2a) is a straight-chain or branched-chain C₁₋₄ alkyl group; R² is a straight-chain or branched-chain C₁₋₄ alkyl group; R³ is a hydrogen atom or a methyl group; at least one of R⁴s is at least one oxygen-containing group selected from the group consisting of oxo groups, hydroxyl groups, alkoxy groups, carboxyl groups, alkoxycarbonyl groups, cycloalkyloxycarbonyl groups, aryloxycarbonyl groups, aralkyloxycarbonyl groups, hydroxymethyl groups, carbamoyl groups, N-substituted carbamoyl groups, and nitro groups.

9. (amended) An acid-responsive compound represented by the following formula (2d) or (2e):



wherein R^3 represents a hydrogen atom or a methyl group; R^4 represents an oxygen-containing group selected from the group consisting of oxo groups, hydroxyl groups, alkoxy groups, carboxyl groups, alkoxy carbonyl groups, cycloalkyloxy carbonyl groups, aryloxy carbonyl groups, aralkyloxy carbonyl groups, hydroxymethyl groups, carbamoyl groups, N-substituted carbamoyl groups, and nitro groups.

10. (amended) A photoresist resin composition comprising (i) a polymer having at least one unit represented by the following formula (11) or (12):



wherein R¹, R², R³, R⁴, the Z rings, and n are as defined in Claim 1 and (ii)
a photoactive acid precursor.

12. (amended) The photoresist resin composition according to Claim 10,
which contains 0.1 to 30 parts by weight of the photoactive acid precursor (ii)
relative to 100 parts by weight of the polymer (i).

13. (amended) The photoresist resin composition according to Claim 8,
wherein the polymer is a copolymer.

D4
G5

14. (amended) A method of forming a pattern, which method comprises
subjecting a layer comprising the photoresist resin composition of Claim 8
formed on a substrate to pattern exposure and
developing the exposed coating layer to form a pattern.

*Attached hereto is a marked-up version of the changes made to the
application by this Amendment.*